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## (54) ACTIVE MATRIX TYPE LIQUID CRYSTAL DISPLAY DEVICE AND ITS MANUFACTURE

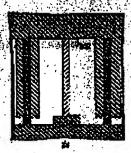
(57) ACTIVE MATRIA TITE alterno.

(57) Abstract:

PROBLEM TO BE SOLVED: To remarkably expand the tolerance for religioning upper and lower substrates by physicing the opening ratio in a leading upper and lower substrates by physicing the opening ratio in a leading of the substrate.

(60) ITTON: In this setive matrix type Sould crystal display device, a display aleatrode 104, a reference electrode 105, a scenning signal line 102 as video signal line 103 and an active element are provided in each pixel area of surfaces of liquid crystal layer sides of transperent cubstrates disposed to face oppositely each other via a liquid crystal layer and light beams transmitting the liquid parallel with the transparent modulated by generating the electric field parallel with the transparent substrates in the liquid crystal layer by a voltage to be impressed. substrates in the liquid crystal layer by a voltage to be impressed between the display electrode 104 and the reference electrode 105. Then the device has the reference electrode 105 adjacently arranged to the video eignal line 103, has an insulated layer between the video signal line 103 and the efficiently stranged reference electrode 105 and also has a structure in which the video signal line 103 and the reference electrode 105 have a superposed part and a light shielding layer 202 is arranged only in the direction perallel with the scanning signal line 102 in the pixel display area.





## LEGAL STATUS

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